

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Ogata et al.
Appl. No. : 10/588,866
Filed : August 9, 2006
For : POLYMER COMPOUND,
PHOTORESIST COMPOSITION
INCLUDING THE POLYMER
COMPOUND, AND RESIST
PATTERN FORMATION
METHOD
Examiner : Walk, A.
Group Art Unit : 1795

RESPONSE TO OFFICE ACTION

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In response to the Office Action mailed **September 22, 2008**, please consider the following remarks.

The listing of claims begins on page 2 of this paper. No amendments have been made.

Remarks begin on page 4 of this paper.